

EQUIVDOC INC 'J62269140'

***** Item Number 1 of 1 *****

DESCRIP :: PATENT
TITLE :: Three-layered pattern formation - includes coating base with organic high molecular cpd., coating with mixt. of organosilane hydrolyzate and colloidal silica and/or silane,
ASSIGNEE :: MATSUSHITA ELEC IND KK; NIPPON SYNTH RUBBER
ACCNNO :: 205253
DATE :: Nov 21, 1987
ABSTRACT :: < BASIC> JP62269140 Method includes (a) coating the uneven base surfac with the organic high molecular cpd. to make a flat surface, (b) coating the organic high molecular cpd. with the coating agent obtd. by mixing the hydrolyzate of organosilano cpd. of formula: $R_1Si(OR_2)_3$ (R_1 is 1-8C organic gp.; R_2 is 1-5C alkyl or 1-4C acyl), and colloidal silica and/or silane cpd. of formula $Si(OR_2)_4$ or its polycondensate of the water and hydrophilic organic solvent, or coating agent obtd. by mixing at least one silane cpd., its hydrolyzate and partial polycondensate of the hydrolyzate, and at least one zirconium cpd. of formula $Zr(OR_2)_4$, hydrolyzate of zirconium cpd. and partial polycondensate of the hydrolyzate, (c) hardening the coating agent to form a hardened film, (d) forming a resist pattern onto the hardened film, (e) etching the hardened film while using the resist pattern as the mask, and transferring the pattern onto the hardened film, and (f) etching the organic high molecular cpd. film while using the hardened film pattern as the mask. ADVANTAGE - The three-layered structure can be stably mfd., and the pattern of upper layer resist can be accurately transferred onto the high molecular cpd. film. @(9pp Dwg.No.0/0)@
PNBASIC :: J62269140
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